

Appl. No. 09/699,897

### In th Claims

Claims 1-27 (cancelled)

28. (currently amended) A PVD component consisting essentially of a material having a face-centered cubic crystalline structure, the component being produced by the method comprising inducing a sufficient amount of residual stress in the component to increase magnetic pass through flux exhibited by the component during PVD compared to pass through flux exhibited ~~prior to~~ without inducing the stress.

29. (previously presented) A sputter component produced by the method comprising:

unidirectionally first cold working a component blank to at least about an 80% reduction in cross-sectional area, the component blank consisting essentially of a material having a face-centered cubic crystalline structure;

heat treating the cold worked component blank at least at about a minimum recrystallization temperature of the component blank; and

inducing a sufficient amount of stress in the heat treated component blank to increase magnetic pass through flux exhibited by the heat treated component blank compared to pass through flux exhibited prior to inducing the stress.

**Appl. No. 09/699,897**

30. (currently amended) A sputter target produced by the method comprising:  
unidirectionally first cold rolling a target blank consisting essentially of nickel to at least about an 85% reduction in cross-sectional area;

heat treating the first cold rolled target blank at a temperature between about 427 °C (800 °F) to about 482 °C (900 °F) for less than about 60 minutes; and

second cold rolling the heat treated target blank to a reduction in cross-sectional area of about 10% of the heat treated ~~component~~ target blank, at least about 70% of a surface area at least within selected boundaries of a surface of the second cold rolled target blank exhibiting a (200) texture.

31. (original) A PVD component consisting essentially of nickel exhibiting a (200) texture over at least about 50% of a surface area at least within selected boundaries and having a sufficient amount of residual stress to exhibit higher magnetic pass through flux compared to pass through flux exhibited absent such stress.

32. (original) The component of claim 31 wherein the selected boundaries define a representative test area.

33. (previously presented) The component of claim 31 wherein the nickel exhibits an average grain size of less than about 50 microns.

34. (previously presented) The component of claim 28 comprising a majority crystallographic structure of (200).

35. (previously presented) The component of claim 28 wherein the induced stress alone is not sufficient to substantially alter surface grain appearance.

**Appl. No. 09/699,897**

36. (previously presented) The component of claim 28 wherein the component consists essentially of nickel.

37. (previously presented) The component of claim 28 wherein the material exhibits an average grain size of less than about 50 microns.

38. (canceled).

39. (previously presented) The component of claim 29 wherein the heat treated component blank comprises a majority crystallographic structure of (200).

40. (previously presented) The component of claim 29 wherein the induced stress alone is not sufficient to substantially alter surface grain appearance.

41. (previously presented) The component of claim 29 wherein the component blank consists essentially of nickel.

42. (previously presented) The component of claim 29 wherein the stress-induced component blank exhibits an average grain size of less than about 50 microns.

43. (previously presented) The target of claim 30 wherein the second cold rolling comprises unidirectionally rolling in the same direction as the first cold rolling.

*Appl. N . 09/699,897*

44. (new) A PVD component consisting essentially of material having a face-centered cubic crystalline structure, the material exhibiting a (200) texture over at least about 70% of a representative surface area, having a sufficient amount of residual stress in the component to increase magnetic pass through flux exhibited by the component during PVD compared to pass through flux exhibited without inducing the residual stress, but such induced residual stress alone not being sufficient to substantially alter surface grain appearance.

45. (new) A PVD component produced by the method comprising:  
unidirectionally first cold working a component blank consisting essentially of a material having a face-centered cubic crystalline structure to at least about an 80% reduction in cross-sectional area;  
heat treating the first cold worked blank at a temperature between about 371°C (700°F) to about 649°C (1200°F) for less than about 60 minutes; and  
unidirectionally second cold working the heat treated blank to a reduction in cross-sectional area of between about 5% to about 15% of the heat treated blank thereby inducing a sufficient amount of residual stress in the blank to increase magnetic pass through flux exhibited by the component during PVD compared to pass through flux exhibited without inducing the residual stress, at least about 70% of a surface area of the second cold worked blank exhibiting a (200) texture and the induced residual stress alone not being sufficient to substantially alter surface grain appearance.